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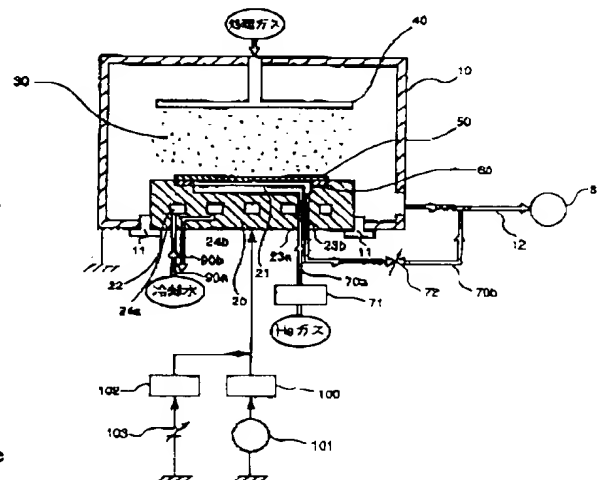
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(54) SAMPLE HOLDING METHOD FOR VACUUM PROCESSING SYSTEM

(57)Abstract:

PURPOSE: To control the temperature of a sample being subjected to vacuum processing effectively and to suppress the effect of heat conduction gas on the process.

CONSTITUTION: A sample 50 being subjected to vacuum processing is mounted on a sample stage in a vacuum processing chamber 10. The sample is held onto the sample stage while being attracted electrostatically and a heat conduction gas is then fed between the rear side of the sample and the sample stage. Supply of the heat conduction gas may be interrupted before the residual attraction force of the sample is removed. This method prevents deformation of the sample due to the pressure of heat conduction gas and restrains increase of the gap between the rear side of the attracted sample and the sample stage while controlling the temperature of the sample effectively.



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